

# WEST Search History

DATE: Saturday, December 28, 2002

<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
		result set	
	<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>		
L21	(SiONH or (silicon with oxygen with nitrogen with hydrogen)) and (ARC or DARC or BARC or (antireflect\$3) or (anti reflect\$3)) and (refractive index) and ((extinction or absorbtion or absorption) coefficient)	13	L21
	<i>DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>		
L20	semiconductor and ((N2 or nitrogen or "N.sub.2" or oxygen or O2 or "O.sub.2") with (thermal or heat\$3 or bake or baked or baking or anneal\$3) with (ARC or DARC or BARC or antireflect\$3 or (anti reflect\$3) or SiON or SiONH or (silicon oxynitride) or SiONx or (silicon and hydrogen and oxygen and nitrogen)))	698	L20
	<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>		
L19	semiconductor and ((N2 or nitrogen or "N.sub.2") with (thermal or heat\$3 or bake or baked or baking or anneal\$3) with (densif\$10) with (ARC or DARC or BARC or antireflect\$3 or (anti reflect\$3) or SiON or SiONH or (silicon oxynitride) or SiONx or (silicon and hydrogen and oxygen and nitrogen)))	4	L19
L18	6444588.pn. and (polysilicon or (polycryst\$8 near2 silicon) or SiN or (silicon nitride) or SiNx)	1	L18
L17	L15 and (polysilicon or (polycryst\$8 near2 silicon) or SiN or (silicon nitride) or SiNx)	28	L17
	<i>DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>		
L16	((((antireflect\$3) or (anti reflect\$3)) near5 (coat\$3 or film or layer or material)) or ARC or DARC or BARC) and (SiO2 or "SiO.sub.2" or (silicon dioxide) or silica or SiON or SiONH or (silicon oxynitride) or (silicon with oxygen with nitrogen with hydrogen)) and ((heat\$3 or bake or baked or baking or anneal\$3) with (((optic\$4 propert\$3) or n or k or (refractive index) or (extinction coefficient)) with (increas\$3 or decreas\$3 or change or changed or changing or alter\$6 or modif\$8 or improv\$3)))	11	L16
	<i>DB=USPT,PGPB; PLUR=YES; OP=ADJ</i>		
L15	L14 not L13	76	L15
L14	((((antireflect\$3) or (anti reflect\$3)) near5 (coat\$3 or film or layer or material)) or ARC or DARC or BARC) same (SiO2 or "SiO.sub.2" or (silicon dioxide) or silica or SiON or SiONH or (silicon oxynitride) or (silicon with oxygen with nitrogen with hydrogen)) and ((heat\$3 or bake or baked or baking or anneal\$3) with (((optic\$4 propert\$3) or n or k or (refractive index) or (extinction coefficient)) with (increas\$3 or decreas\$3 or change or changed or changing or alter\$6 or modif\$8 or improv\$3)))	91	L14

L13	L12 and ((heat\$3 or bake or baked or baking or anneal\$3) same (((optic\$4 propert\$3) or n or k or (refractive index) or (extinction coefficient)) with (increas\$3 or decreas\$3 or change or changed or changing or alter\$6 or modif\$8 or improv\$3)))	57	L13
L12	L6 and ((ARC or (antireflect\$3) or (anti reflect\$3)) near5 (coat\$3 or film or layer or material))	626	L12
L11	L4 and L5	15	L11
L10	L9 and (ARC or (antireflect\$3) or (anti reflect\$3))	33	L10
L9	L3 and L5	89	L9
L8	L3 and L4	3	L8
L7	L3 and L4 and L5	0	L7
L6	L3 or L4 or L5	5111	L6
L5	(427/372.2).icls. or (427/376.2).icls. or (427/397.7).icls. or (427/402).icls. or ((427/419.2 )!.ICLS. )	2842	L5
L4	(427/255.29).icls. or (427/255.37).icls. or (438/764).icls. or (438/786).icls. or (438/787).icls. or (438/788).icls. or (438/791).icls. or ((438/29 )!.ICLS. )	1167	L4
L3	(427/162).icls. or (359/580).icls. or (359/581).icls. or ((359/586 )!.ICLS. )	1209	L3

*DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ*

L2	(Chiou or Jang or (Taiwan Semiconductor)) and ((heat\$3 or bake or baked or baking or anneal\$3) same ((refractive index) or (extinction coefficient)))	8	L2
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*DB=USPT,PGPB; PLUR=YES; OP=ADJ*

L1	(Chiou.in. or Jang.in.) and ((heat\$3 or bake or baked or baking or anneal\$3) with ((refractive index) or (extinction coefficient)))	6	L1
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END OF SEARCH HISTORY